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Evactron® 45 De-Contaminator

electron microscope cleaning technology to improve resolution and imaging time for 21st century needs.

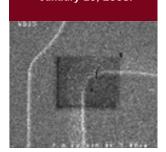
Evactron® D-C cleaning uses a unique, cutting edge process for remote plasma production of oxygen radicals that flow downstream through your system, removing hydrocarbons.

These new user friendly Evactron® D-C models optimize remote plasma cleaning perfectly to the needs of the user.

Gentle, Fast, Convenient and Effective Cleaning

- Easy to operate and setup
- Start cleaning by using vent and evacuation controls for chamber.
- Preset pressure, power, and time settings from front panel or computer interface
- · Uses air, no special gases needed
- Plasma and nitrogen purge cleaning can be combined in cycles for maximum cleaning efficiency
- Advanced plasma detection logic
- Cleaning and error logs record cleaning history and aids trouble shooting
- Rackmounted
- Electronic Chassis: H 3.5" x W 19.5" x D 7"
- RF Power: 5 20 Watts at 13.56 MHz
- KF 40 vacuum mounting flange
- 100-240 VAC 50/60 Hz input

Try the Evactron®
Process in your lab, free,
[shipping charges apply]
for 30 days by placing an
evaluation PO by
January 15, 2008.



Unwanted Artifact



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After Evactron Cleaning